

secondly, feeding a nitrous oxide (N₂O) gas into a reactor;

thirdly, generating a plasma in said reactor; and

fourthly, removing a portion of said organic compound to generate said organic plug within said via.

OC.
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Claim 16 (currently amended). The method of claim ¹⁵~~16~~ further comprising generating a gas mixture by mixing a diluent with said N₂O gas ~~said N₂O gas~~, and applying said gas mixture to said reactor.

Claim 17 (original). The method of claim 16 wherein said diluent is a noble gas.

Claim 18 (original). The method of claim 16 wherein said silicon containing dielectric material is selected from a group consisting of organosilicate glass (OSG), silicon dioxide (SiO₂), and fluorinated silicate glass (FSG).

Claim 19 (original). The method of claim 18 wherein said method for generating said organic plug is applied during one of a plurality of steps performed during a dual damascene process.